



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant(s): Annapragada et al. |) | Group Art Unit: 2813 |
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| Application Serial No.: 10/712,326 |) | Examiner: Nguyen, Thanh T |
| |) | |
| Filed: November 12, 2003 |) | |
| |) | |
| Title: Minimizing the Loss of Barrier |) | |
| Materials During Photoresist |) | |
| Stripping |) | |
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AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir/Madam:

This Amendment and Response is submitted in response to the Office Action dated May 16, 2005 in the above referenced patent application. A one-month extension is filed herewith. Please enter and consider the following amendments and remarks.

Amendments to the Claims are reflected in the listing of claims which begins on Page 2 of this paper.

Remarks begin on page 8.